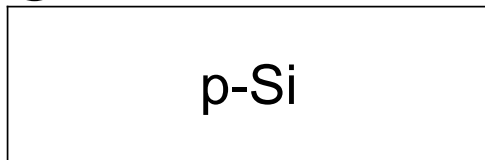
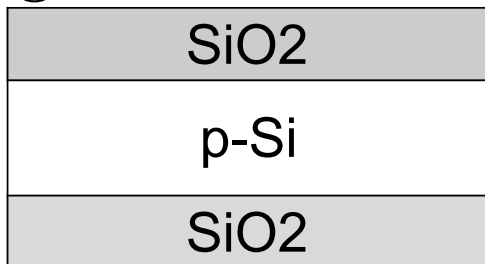


①



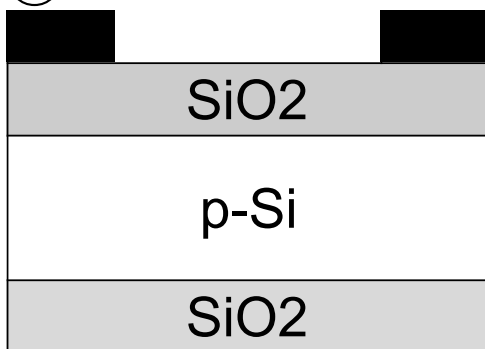
↓ 熱酸化

②



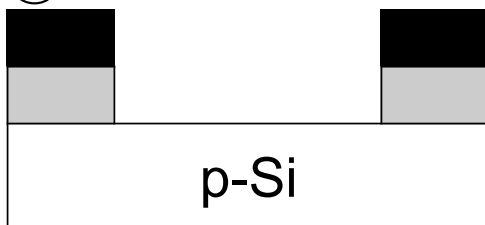
↓ フォトリソグラフィ

③



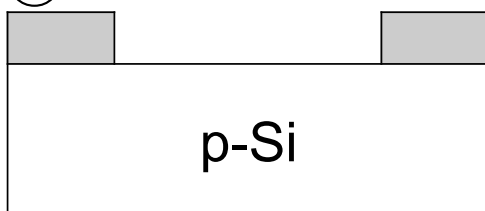
↓ SiO2膜のエッチング

④



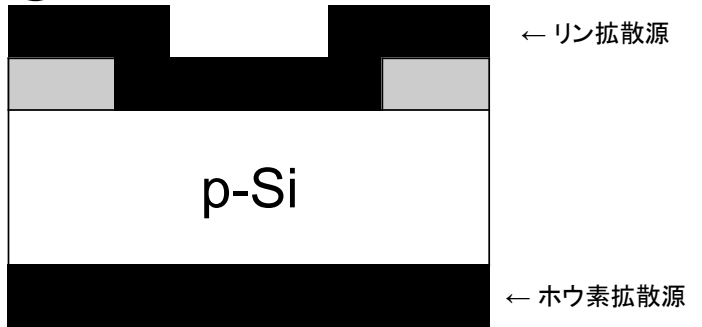
↓ フォトレジストの除去

⑤



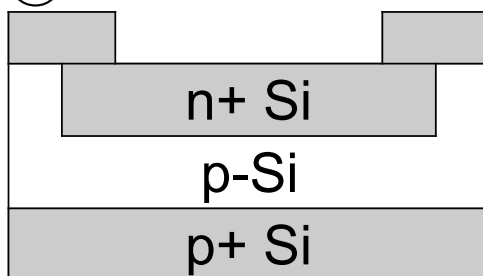
↓ 拡散源の塗布

⑥



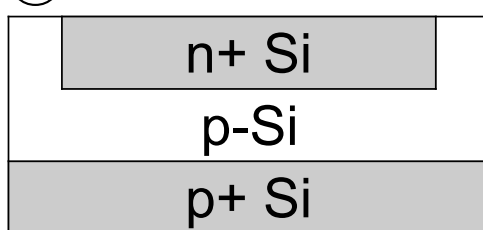
↓ 熱拡散+拡散源除去

⑦



↓ SiO2膜除去

⑧



↓ 電極の形成

⑨

